

Supplementary information for

Influence of ammonia annealing on Cr-N thin films and their thermoelectric properties

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Figure S1 presents the full range XRD pattern of the as grown and annealed samples from the two samples series. The 10x10 mm² samples were cut in half making the XRD holder visible on the XRD pattern with a peak at 25 ° coming from the XRD holder. No other peaks than the ones the 111 peak and its higher order 222 from CrN are visible.

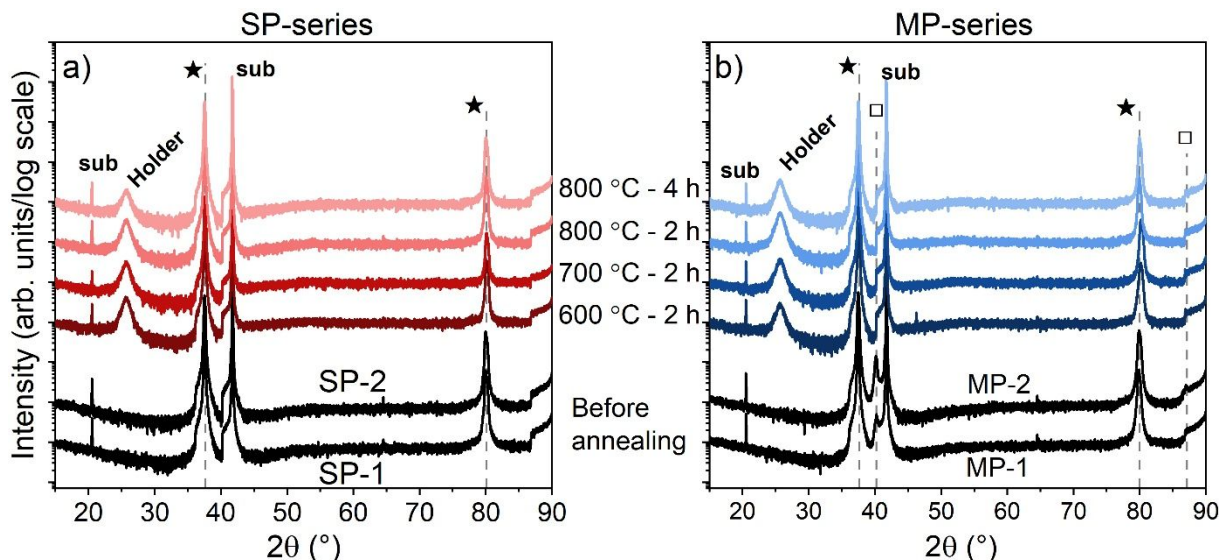


Figure S1: XRD $\theta/2\theta$ scans of as-grown and annealed films from a) the SP series and from b) the MP-series. For both panels, the bottom two patterns are XRD scans from as-grown films. Marked reflections, star: cubic CrN 111; square: hexagonal Cr₂N 0002; sub: Al₂O₃ 0006; and holder: diffuse diffraction from the XRD holder.